

# Supporting Information

## Intrinsic Vacancy in 2D Defective Semiconductor $\text{In}_2\text{S}_3$ for Artificial Photonic Nociceptor

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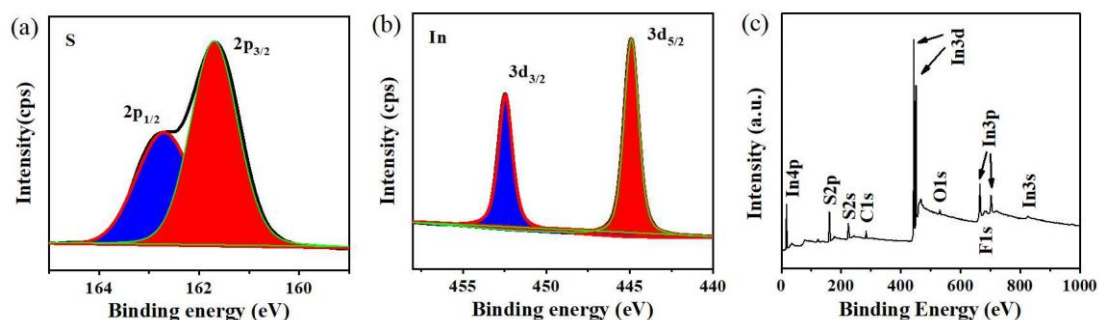


Figure S1. XPS spectrums of as-grown  $\text{In}_2\text{S}_3$  nanosheet.

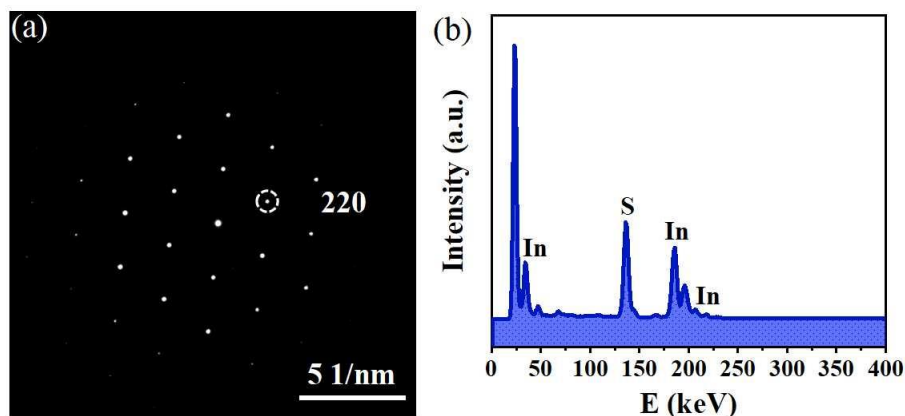
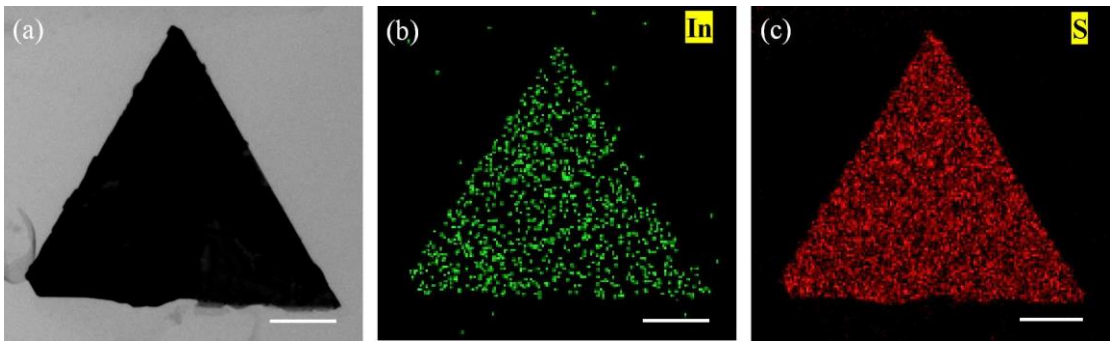
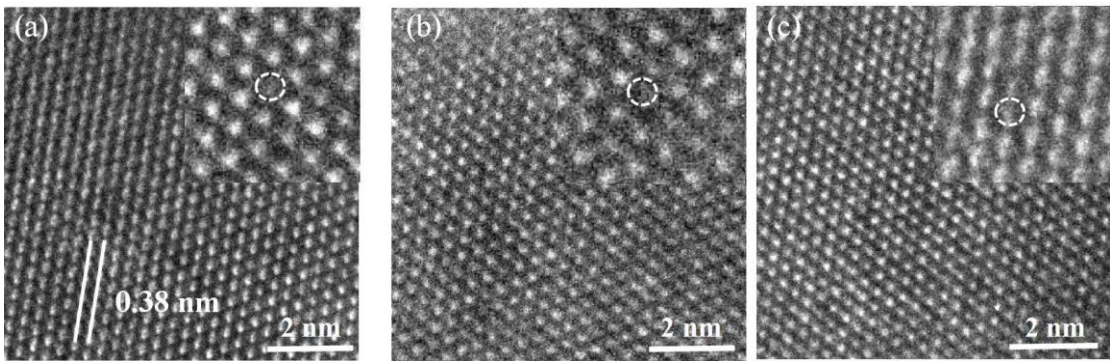


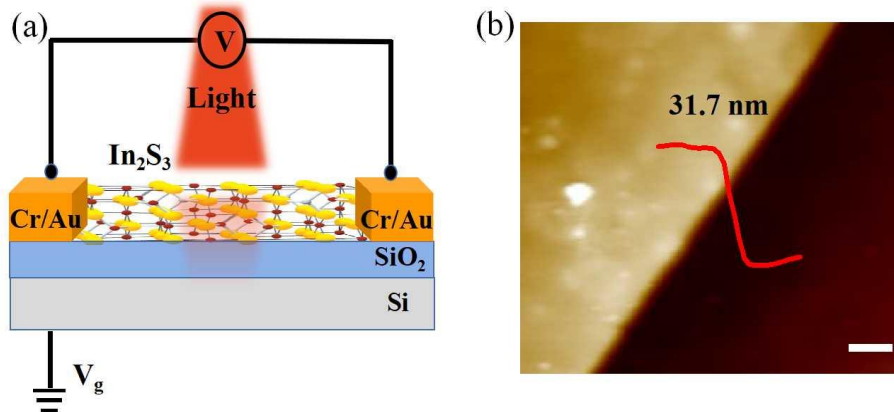
Figure S2. (a) The SAED pattern and (b) the EDS spectrum of the  $\text{In}_2\text{S}_3$  nanosheet.



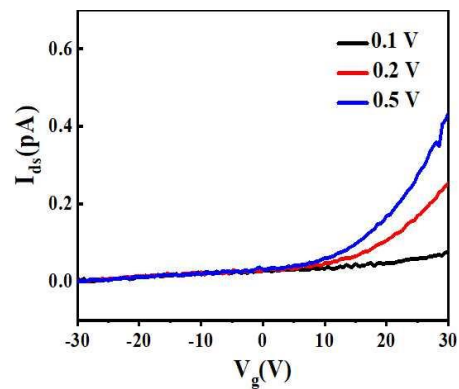
**Figure S3.** (a) Low-resolution TEM, (b) In-K and (c) S-K edges mapping images of the  $\text{In}_2\text{S}_3$  triangular nanosheet (Scale bar: 1  $\mu\text{m}$ ). In and S elements have good uniformity, indicating a uniform distribution of defects.



**Figure S4.** HRTEM images of different positions of  $\text{In}_2\text{S}_3$  nanosheet with the lattice spacing of 0.38 nm corresponds to the (220) crystal planes. The vacancy-defects highlighted by white circles.

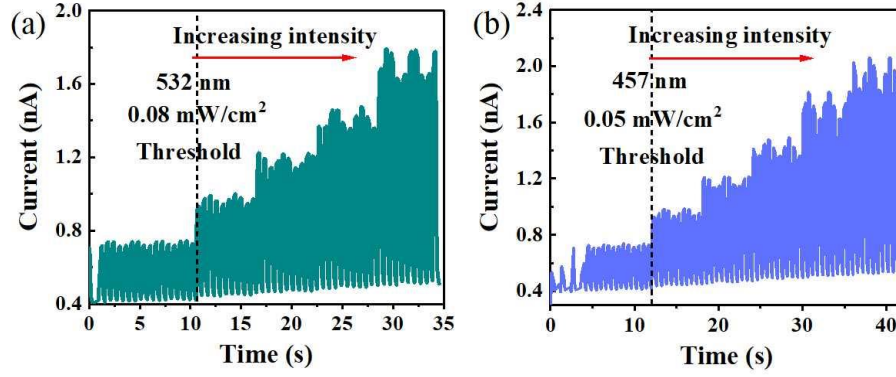


**Figure S5.** (a) Schematic diagram of  $\text{In}_2\text{S}_3$  device. (b) The thickness of the  $\text{In}_2\text{S}_3$  in the device (Scale bar:  $0.5 \mu\text{m}$ ).

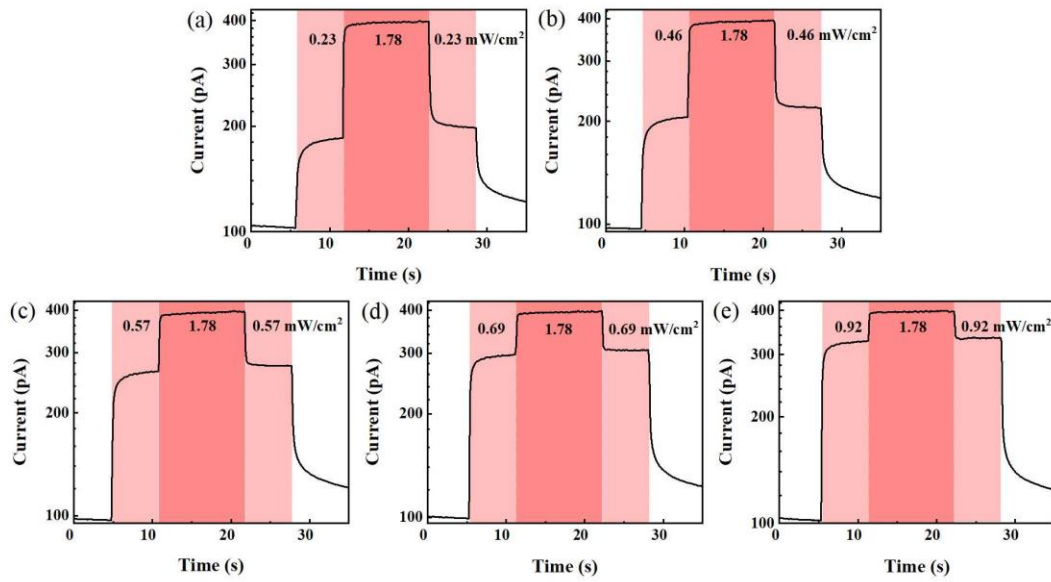


**Figure S6.** The transfer curves of  $\text{In}_2\text{S}_3$  devices.

From the transfer curves of the  $\text{In}_2\text{S}_3$  nanosheet, when sweeping  $V_g$  from  $-30$  V to  $30$  V with different  $V_{ds}$ ,  $I_{ds}$  in the channel increases significantly, when applying more positive gate voltages to inject electrons into the  $\text{In}_2\text{S}_3$  crystals, which indicates a typical n-type semiconducting behavior.



**Figure S7.** Threshold characteristics of the device under 532 nm and 457 nm optical pulses.



**Figure S8.** The photoresponse characteristics of the  $\text{In}_2\text{S}_3$  device after the different light intensity illuminations.